

L Number	Hits	Search Text	DB	Time stamp
1	2	((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and (neon same (flow or flowrate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:22
2	21	430/313.cor. and 430/328.cxr.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:25
3	16	((((post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) not ((silicon or Si) near3 (wafer or substrate))) and etch\$3	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:33
4	3	((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:36
6	0	(430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:40
7	11	((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) same (flow or flowrate or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:46
8	1	((430/328.ccls. not 430/313.cor.) and ((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:49
9	20	((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:54
10	0	((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not ((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:00

11	586	((430/328.ccls. not 430/313.cor.) not (((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not (((430/328.ccls. not 430/313.cor.) and ((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:15
12	377	430/313,317.ccls. not (430/328.ccls. not 430/313.cor.)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:40
13	1	(((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and (Ne)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:43
14	1	(((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and neon	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:44
15	0	((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and (neon same (flow or flowrate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:46
16	102	((ultraviolet or uv) with (Ne)) same (inert or Ar or argon)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:47
17	4	((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:56
18	71	((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 16:00
19	4	430/313.cor. and 430/328.cxr. and (etch\$3 with chamber)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 16:06

22	4	250/504R-504H.ccls. and (neon or Ne) with (ultraviolet or uv)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 16:09
-	2	((("20030003407") or ("20030003683"))).PN.	USPAT; US-PGPUB	2003/01/25 17:17
-	25384	(resist or photoresist or photopolymer\$7) near3 (develop\$3)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 17:10
-	1494	((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 12:06
-	38757	(Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 12:07
-	58	((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 12:07
-	391	(ultraviolet or uv) with (neon)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/15 10:10
-	57	((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/15 10:11
-	2	((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist)) and (neon same (flow or flowrate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:19
-	203	((ultraviolet or uv) with (neon)) same (inert or Ar or argon)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/15 10:12
-	51	((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3)) and etch\$3	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 15:49
-	1644	(resist or photoresist or photopolymer\$7) and ((develop\$3) adj20 (ultraviolet or uv))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 17:12
-	84	((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3)) and ((resist or photoresist or photopolymer\$7) and ((develop\$3) adj20 (ultraviolet or uv)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 17:14
-	583	430/328.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/01 14:11
-	16	430/313.cor. and 430/328.cxr.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:25
-	181	(post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 18:11
-	49	((post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer\$7 or photopolymer\$7 or photoresist or resist))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 18:14

-	21	((post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) not ((silicon or Si) near3 (wafer or substrate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 18:30
-	15	((post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) not ((silicon or Si) near3 (wafer or substrate))) and etch\$3	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:31
-	9	"4751170" "4931351" "5407786" "5427649" "5486424" "5688723" "5707783" "5877075" "6190837").PN.	USPAT	2003/02/01 10:33
-	567	430/328.ccls. not 430/313.cor.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/01 14:36
-	1	((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:35
-	12	(430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:39
-	11	((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) same (flow or flowrate or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:46
-	1	((430/328.ccls. not 430/313.cor.) and ((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:49
-	329	((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/01 15:31
-	66	((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/01 16:50
-	15	((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:52

-	51	((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not ((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:00
-	554	(430/328.ccls. not 430/313.cor.) not (((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not (((430/328.ccls. not 430/313.cor.) and ((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not (((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not (((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not (((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:11
-	1984	430/313,317.ccls. not (430/328.ccls. not 430/313.cor.)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:39
-	1	(((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and (Ne)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:43
-	1	(((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and neon	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:44
-	304	(ultraviolet or uv) with (Ne)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/15 10:10
-	0	((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist)) and (neon same (flow or flowrate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:45

-	83	((ultraviolet or uv) with (Ne)) same (inert or Ar or argon)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:46
-	3	((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPÄT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:55
-	1	("6054379").PN.	USPAT; US-PGPUB	2003/02/21 17:30
-	58	((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:58
-	3	430/313.cor. and 430/328.cxr. and (etch\$3 with chamber)	USPÄT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 16:06
-	143	430/313,317.ccls. and (etch\$3 with chamber) not (430/328.ccls. not 430/313.cor.)	USPÄT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/22 17:13
-	101	430/313,317.ccls. and (etch\$3 near3 chamber) not (430/328.ccls. not 430/313.cor.)	USPÄT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/22 17:19
-	2231	(resist or photoresist) same ((ultraviolet or uv) with etch\$3)	USPÄT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/22 17:23
-	175	((resist or photoresist) same ((ultraviolet or uv) with etch\$3)) and 430/313,317,328.ccls.	USPÄT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/22 17:22
-	17	(resist or photoresist) same ((ultraviolet or uv) with etch\$3 near2 chamber)	USPÄT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/22 17:23
-	4	250/504R-504H.ccls. and (neon or Ne) with (ultraviolet or uv)	USPÄT; US-PGPUB	2003/08/21 16:07